L	Hits	Search Text	DB	Time stamp
Number 1	2898	plasma ad density		
	2090	plasma adj density	USPAT	2004/02/05
2	1911	(plasma adj density) and semiconductor	USPAT	2004/02/05
3	2028	Land to the state of the state		09:09
3	1018	([plasma adj density] and semiconductor) and (oxygen or O?sub.2)	USPAT	2004/02/05
4	545	(((plasma sdj density) and semiconductor)	USPAT	2004/02/05
		and (oxygen or 0?sub.2)) and	OUTAL	09:10
5	12	(photo\$lresist or resist)	1	
,	12	1shihara-Shigenori.in.	USPAT; US-PGPUB;	2004/02/05
	1		EPO; JPO;	11:00
			DERWENT/	
8	2225	(resist or photo\$1resist) same (ash or	1BM_TDB	
		ashing) same (oxygen or 07sub.2)	USPAT	2004/02/05
9	6	((resist or photo\$1resist) same (ash or	USPAT	2004/02/05
	1 .	ashing) same (oxygen or O?sub.2)) and (fluorine near4 "8")		11:02
10	1343	((resist or photo\$lresist) same (ash or	USPAT	2004/02/05
	1010	ashing) same (oxygen or 0?sub.2)) and	UDFAL	11:04
14		(fluorine or CF?sub. 4 or SF?sub. 6)		
11	1100	(((resist or photo\$lresist) same (ash or ashing) same (oxygen or 07sub.2)) and	USPAT	2004/02/05
		(fluorine or CF?sub.4 or SF?sub.6)) and		11:05
		plasma and Say<=2000		
15	578	((((resist or photo\$lresist) same (ash or	USPAT	2004/02/05
		ashing) same (oxygen or O?sub.2)) and (fluorine or CF?sub.4 or SF?sub.6)) and		11:13
,) 1	plasma and @avc=20001 and (done or doning		
		or dopant or implants3 or implantation)		
16	142	(((((resist or photo\$lresist) same (ash	USPAT	2004/02/05
	1 1	or ashing) same (oxygen or O?sub.2)) and (fluorine or C??sub.4 or SP?sub.6)) and		11:14
		plasma and @ayc=2000) and (dope or doping		
	1 1	or dopant or implants3 or implantation))		
		and (photo@lresist or resist or photo@lsensitive).ab.		
1.7	5	["4511430" "5226056" "5503964"	USPAT	2004/02/05
	1	"5795831" "5811358").PN.	ODIA.	11:27
18	15	("4123841" "4514254" "4670091" "4983254" "5077598" "5122225"	USPAT	2004/02/05
	Į I	"4983254" "5077598" "5122225" "5348619" "5358602" "5451291"		11:30
		"5485304" "5497262" "5512507"		
		"5521104" "5526951" "5573971").PN.		
.9	80	((resist or photoSiresist) same (ash or ashing) same (oxygen or 07sub.2)) and	USPAT	2004/02/05
1	1 1	((fluorines or CF2sub.4 or SF2sub.6) with		11:31
		(percent or "%" or percentage()		
0	71	(((resist or photoSiresist) same (ash or	USPAT	2004/02/05
		ashing) same (oxygen or O?sub.2)) and ((fluorine) or CF?sub.4 or SF?sub.6) with		11:32
		(percent or "%" or percentage))) and		
		8ay<=1999		
	3838	(resist or photo\$1resist) same (ash or ashing)	USPAT	2004/01/14
	2210	asning) (resist or photo\$lresist) same (ash or	USPAT	13:41 2004/02/05
		ashing) same (oxygen or O?sub.2)	ANENT	11:01
1	2412	[resist or photo\$lresist] same [ash or	USPAT	2004/01/14
	1	ashing) same (oxygen or O?sub.2 or CO or		13:44
	1045	NO or (nitrogen adj oxide)) ((resist or photo\$lresist) same (ash or	USPAT	2004/01/14
	- 1	ashing) same (oxygen or O?sub.2 or CO or	00174	13:45
		NO or (nitrogen adj oxide))) and (doping	1	
		or depant or implant or implanting or		
		or dopant or implant or implanting or implanted)		

 247	17/7		
247	O'sub.2) with (hydrogens or M'sub.2) with (fluorines))) and (implants3 or ionslimplants3 or doped or doping or	USPAT	2004/01/21 15:22
	dopant) and plasma) and (resist or photo\$lresist or photo\$lsensitive or organic)		
238	((((semiconductor and ((oxygen\$ or O?aub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))] and (implant\$3 or ion\$limplant\$3 or doped or doping or	USPAT	2004/01/21 15:21
	dopant)) and plasma) and (resist or photo\$lresist or photo\$lsensitive or organic)) and @aw=2001		
206	{{{semiconductor and {{oxygen\$ or 0?sub.2} with {hydrogen\$ or H?sub.2} with {fluorine\$})} and {implant\$3 or lon\$limplant\$3 or doped or doping or	USPAT	2004/01/21 15:23
20	dopant) and plasma) and (resist or photo\$1resist or photo\$1sensitive) ("4778536" "5100505" "5108542"	USPAT	2004/01/21
	"5147499" "5160765" "5200361" "5296038" "5298038" "5298112" "5488754" "5628871" "5693147" "5743201" "5810929" "5814155" "581302" "582489" "5885274" "5925577" "6066508").FN.		15:43
8	("5034086" "5226056" "5393374" "5567271" "5792314" "5902134" "6024887" "6043004").pN	USPAT	2004/01/21 16:41
	(resist or photo\$lresist or photo\$lsensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H7amb.2)	USPAT	2004/02/02 11:02
2039	({resist or photo\$lresist or photo\$lsensitive} same (oxygen\$ or 07sub.2) same (hydrogen\$ or H?sub.2)} and plasma	USPAT	2004/02/02 11:01
947	((fresist or photo\$1resist or photo\$1sensitive) same (pxygen\$ or O7sub.2) same (hydrogen\$ or H7sub.2)) and plasma and (fluorine or F7sub.2 or fluoride)	USPAT	2004/02/02 11:01
768	[(((resist or photo\$1resist or photo\$1scnsitive) same (oxygen\$ or OFsub.2) same (hydrogen\$ or Mfsub.2)] and plasma) and (fluorine or Ffsub.2 or fluoride) and ((oxygen\$ or OFsub.2) with	USPAT	2004/02/02 11:06
515	(hydrogens or H?sub.2); (((((resist or photos) resist or photos) sems[tive) same (oxygens or 07sub.2) same (hydrogens or H?sub.2)) and plasme) and (fluorine or P?sub.2 or	USPAT	2004/02/02 11:12
	fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or ion\$limplant\$3)		
	((((((resist or phoco\$iresist or photo\$iresist) or photo\$iresitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or P?sub.2 or fluoride)) and (roxygen\$ or O?sub.2 with (hydrogen\$ or H?sub.21)) and (implant3).	USPAT	2004/02/02 11:05
	or doping or dopant or doped or ion\$limplant\$3)) and Bay<=2001		

_	474	(((((((resist or photo3)resist or	USPAT	2004/02/02
		photo\$lsensitive) same (oxygen\$ or	GOZAL	11:05
	1	(078Ub.2) same (hydrogens or H290b 211 and	1	11.03
		(plasma) and (fluorine or Fraub.2 or		
		fluoride)) and ((oxygens or O2min 2) with	i .	
	1	(hydrogen\$ or H?sub.2))) and (implant\$3		
		or doping or dopant or doped or		1
	1	ion\$limplant\$3)) and Gayc=2001) and		
		semiconductor		
	301	(((((resist or photo\$lresist or	USPAT	2004/02/02
		photo\$lsensitive) same (oxygen\$ or	CDEMA	11:13
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		11:13
	1	plasma) and (fluorine or F?sub.2 or		
	1	fluoride) and ((oxygen\$ or 0°sub.2) with		1
		(hydrogen\$ or H?sub.2))) and ((implant\$3		
	i	or doping or dopant or doped or		
	i	ion\$limplant\$3) same (resist or		
		photo\$lresist or photo\$lsensitive))		
	1 163	(((((resist or photo\$lresist or		
	100	photo\$1sensitive) same (oxygen\$ or	USPAT	2004/02/02
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		11:13
	1	plasma) and (fluorine or F?sub.2 or		
		fluoride)) and ((oxygen\$ or O?sub.2) with		
		(hydrogens or H?sub.2))) and ((implant\$3		
		(inplants)		
		or doping or dopant or doped or		
		ion\$limplant\$3) with (resist or		Į.
	150	photo\$1resist or photo\$1sensitive()		
	136	((((((resist or photo\$lresist or	USPAT	2004/02/02
	1	photo\$1sensitive) same (oxygen\$ or		11:14
		O'sub.2) same (hydrogen\$ or H?sub.2)) and		
		plasma) and (fluorine or F?sub.2 or		1
		fluoride)) and ((oxygens or O?sub.2) with		
		(hydrogen\$ or H?sub.2))) and ((implant\$3		
		or doping or dopant or doped or		
	l .	lon\$limplant\$3) with (resist or		
		photo\$1resist or photo\$1sensitive())) and		
		@ay<=2001		
	145	((((((resist or photo\$lresist or	USPAT	2004/02/02
		photo\$1sensitive) same (oxygen\$ or		11:14
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		
		plasms) and (fluorine or F?sub.2 or		
		fluoride)) and ((oxygen\$ or O?sub.2) with		
		(hydrogen\$ or M?sub.2))) and ((implant\$3		Į.
		or doping or dopant or doped or		
		ion\$limplant\$3) with (resist or		1
		photo\$iresist or photo\$isensitive()) and		
		Eav<=2000		
	1.6	("4063803" "4201579" "4340456"	USPAT	2004/02/02
		"4817558" "4990229" "5122251"		11:16
		"5262610" "5366557" "5397395"		
		"5429070" "5542559" "5625259"		
		"5747917" "5789322" "5824604"		
1		"5895548"), PN.		1
	8	("5034086" "5226056" "5393374"	USPAT	2004/02/02
		"5567271" "5792314" "5902134"	CDIAL	11:35
- 1		"6024887" "6043004"),PN.		11:35

-	970		TUSPAT	2004761714
		ashing) same (exygen or 02 min 2 or 00 or	USPAI	13:45
		NO or (nitrogen add oxide))) and (doming		20.40
			1	
	1	(mplanted)) and plasma		
-	593		USPAT	2004/01/14
		ashing) same (oxygen or 0?sub.2 or CO or		13:47
		NO or (nitrogen adj oxide))) and (doping		
		or dopant or implant or implanting or	i	1
	1	implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or	1	
		"C.sub,2 H.sub,6")		1
	402	({(((resist or photo\$lrasist) same (ash	770000	
		or ashing) same (oxygen or O?sub.2 or CO	USPAT	2004/01/14
		or NO or (nitrogen adj oxide))) and		13:49
		(doping or dopant or implant or		
		implanting or implanted)) and plasma) and		1
		CH7sub, 4 or "C. sub, 2 M. sub, 6"11 and		
		(fluoring or fluoride or NF?sub.3 or		
	1	F?sub.2 or SF?sub.6)		
	348	(((((resist or photo\$lresist) same (ash	USPAT	2004/01/14
	1	or ashing) same (exygen or O?sub.2 or co	1	13:50
		or NO or (nitrogen ad) oxide))) and	1	
		(doping or dopant or implant or]	
		implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or	l	
		CH7sub.4 or "C.sub.2 H.sub.6" and		
		(fluorine or fluoride or NF7sub.3 or		1
	344	(((((((resist or photo\$lresist) same (ash	HSPAT	2004/01/14
	1	or ashing) same (oxygen or O?sub.2 or CO	OBPAL	13:51
		or NO or (nitrogen adj oxide))) and		13:31
		(doping or depant or implant or		
		implanting or implanted); and plasma; and		
		(hydrogen or H7sub.2 or "M. sub.2 O" or		
		CH?sub.4 or "C.sub.2 H.sub.6"11 and		
	1	(fluorine or fluoride or MF7sub.3 or		
		F?sub.2 or SF?sub.6)) and @ay<=2000) and		
	101	(boron or phosphorus or arsenic or As!)	l	1
	101	((((((((resist or photo\$lresist) same	USPAT	2004/01/14
		(ash or ashing) same (oxygen or 07sub.2		13:52
		or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or		1
		implanting or implanted)) and plasma) and		A.
		(hydrogen or H?sub.2 or "H.sub.2 O" or		
		CHPsub.4 or "C.sub.2 H.sub.6"1) and		
	1	(fluorine or fluoride or NF7sub.3 or		1
	1 1	F?sub.2 or SF?sub.6)) and @ayc=2000) and		1
		(bogon or phosphorus or armenic or acti)		
	1			1
	14		USPAT	2004/01/14
	1			14:50
	1	"5298112" "5382316" "5401322"		1
		"5403436" "5643474" "5651860"		
		"6024801" "6149828").PW.		
	657	semiconductor and ((oxygen8 or 0°sub.2)	USPAT	2004/01/21
		with (hydrogen\$ or H?sub.2) with		15:16
	360	(fluorines))		
		(semiconductor and ((oxygen\$ or 0?sub.2) with (hydrogen\$ or H?sub.2) with	USPAT	2004/01/21
		(fluorines))) and (implants3 or		15:19
		ion\$limplant\$3 or doped or doping or		
				1
	322	((semiconductor and ((oxyment or ozent 3)	TTO DOM	2004/01/21
			OSPAC	15:19
		(fluorine\$))) and (implant\$3 or		13:15
		ionSlimplant\$3 or doped or doping or		
	1	dopant)) and plasma		1